

IN THE SPECIFICATION

Please amend the specification to as shown below:<sup>1</sup>

Please amend the paragraph on page 1, at lines 21-27, to read as shown below:

C1  
Conventionally, in a lithography process which is a process in manufacturing a semiconductor device, various exposure apparatuses are used to transfer a circuit pattern formed on a mask or a reticle (hereinafter, generically referred to a "reticle") onto a substrate such as a wafer, or glass plate or the like that is coated with a resist (photoresist).

Please amend the paragraph on page 66, at lines 3-11, to read as shown below:

C2  
A reticle fine movement stage not shown in the drawings is arranged on the reticle stage RST to finely drive the reticle R in a non-scanning direction (in the X-direction) while chucking and holding the reticle R. However, driving operation of the reticle R in the non-scanning direction is almost never concerned with the present invention and, therefore, a description of a driving system in the non-scanning direction is omitted in the following.

IN THE CLAIMS

Please cancel Claim 30 without prejudice.

<sup>1</sup> The changes to the specification are shown using underscoring and bracketing in the attachment hereto.